

Index

a

advanced photodetectors 11, 14, 44
amplification process 123
amplified/active feedback lasers (AFLs) 224, 225
angular velocity sensitivity 144–151

b

beat note locking (BNL) 126
broadband photodetectors 26
electron-hole pairs 30
enhanced charge transport 35
Ga-based semiconductors 34
light-sensitive spectral region 30
mobility 26
semimetallic 2D TMDs 34
2D materials-based devices 35
ultrathin BP-based photodetectors 27
wide detectable range 26

c

carrier-photon resonance (CPR) effect 218
chemical vapor deposition (CVD) 2, 6, 14, 87
Chirp suppression 216, 238, 259
coherent modulation locking (CML) 126
coherent transfer function (CTF) 178
confocal laser scanning microscopy (CLSM) 175

d

data signal source 94–98, 107–111
density functional theory (DFT) 28
detectivity (D) 12, 14, 36, 49
Drude model 56–57

e

electromagnetic spectrum 13
electro-optic conversion characteristics 229–238, 259
EM materials 56
evanescent-waves 177–182, 184–186, 188, 189, 191–193, 195, 198, 206, 207
external injection locking 245–246

f

fabrication process 39, 75, 93, 180, 184, 185, 193, 206, 221, 222, 229, 260, 261
far-field microscopy 176
finite-difference time-domain (FDTD) method 37, 94, 203
flexible photodetectors 44–49
fluorescence photoactivation localization microscopy (FPALM) 176
focal plane arrays (FPA) 55
Fourier ptychographic microscopy (FPM) 176
frequency-modulated microwave signal generation 248–250

g

- graphene optical switch 85–87
 AC mode of the gate capacitor 89–93
 DC mode of the gate capacitor 87–89
 optical features 85
 graphene-assisted PSIM 202–203

h

- heterostructure all-optical switch 93, 94,
 100–102
 high-performance microwave signal
 generation optimizing technique
 250–254
 hyperbolic metamaterials (HMMs) 204

i

- infrared (IR) photodetectors 21–25,
 55–78
 integrated microwave photonics (IMWP)
 215–261
 intensity-difference noise power (IDNP)
 161

k

- Kerr effect 90, 105, 108

l

- laser arrays 218, 256–259
 localized plasmonic structured
 illumination microscopy (LPSIM)
 177
 localized plasmon-assisted illumination
 nanoscopy 203–204
 localized surface plasmonic waves (LSPR)
 36, 68
 circular disk array 71–72
 nanowire pair 69–71
 near-field distributions 68–69
 low-pass filters (LPFs) 127

m

- Mach-Zehnder interferometer (MZI)
 84, 123
 metal-dielectric multilayer metasubstrate
 PSIM 200–202

- metamaterial assisted illumination
 nanoscopy 204–206
 microwave photonic filter (MPF) 218,
 254–256
 microwave photonics (MWP) 215
 characteristics 215, 216
 integration 216
 mixed-dimensional heterostructures 23,
 25
 mode-beating self-pulsations (MB-SPs)
 218, 242–244
 modulation response enhancement 216,
 229–236
 monolithically integrated multi-section
 semiconductor lasers (MI-MSSLs)
 215–261
 monolithically integrated mutually
 injected semiconductor lasers
 (MI-MISLs) 217, 225–229
 monolithically integrated optical feedback
 lasers (MI-OFLs) 219–220
 multiwall carbon nanotubes (MWCNTs)
 182, 184

n

- nanofabrication technologies 55
 near-field scanning optical microscopy
 (NSOM) 177
 noble-metal dichalcogenides 22, 49
 nonlinear distortions 229, 237, 238, 257
 nonlinear interferometer 124–143
 entanglement 136–143
 hybrid interferometer 151–155
 interference-induced quantum
 squeezing enhancement 160–163
 phase locking 125–131
 phase sensitivity 131–136
 phase-sensitive parametric amplifier
 155–160
 quantum noise cancellation 136–143
 types 143
 nonlinear interferometric SPR sensing
 124, 164–173
 nonlinear refractive index coefficient (n_2)
 95

- nonlinear Sagnac interferometer (NSI) 124, 143–151
- nonresonant transmission wave 63
- numerical aperture (NA) 175
- NW ring illumination microscopy (NWRIM) 179
- o**
- optical devices 83, 84, 115
- optical injection systems 225–227, 244, 245
- optical interferometer 123
- optical microscopy 175–177, 193
- optical modulators 85, 104, 105, 111, 112
- optical nonlinearity 84, 105
- optical resistance switch
- graphene 85–93
 - modulation characteristics 104–115
 - nanomaterial heterostructures based switch 93–104
- optical signal 105, 219, 221, 231, 246
- optical transfer function (OTF) 177–179, 201
- Otto configuration 59, 60
- p**
- parallel cases 142, 143
- passive feedback lasers (PFLs) 218, 220–224, 231
- phase-locking techniques 125, 131, 143
- photoactivated localization microscopy (PALM) 176
- photobolometric effect 11, 12
- photoconductive effect 11, 12, 20, 30
- photodetection mechanisms 11, 12, 20
- photonic band-gaps (PBGs) 83
- photonic crystal (PC) 83
- photonic integration circuits (PICs)
- technology 215
- photonic microwave 218, 234, 238–254, 256, 259, 261
- photoresponsivity 12, 14–17, 21, 22, 26, 28, 30, 34–36, 38, 40, 41, 43, 44, 46, 48
- photothermoelectric effect 11, 12, 30
- photovoltaic effect 11, 12, 34
- piezo-electric transducers (PZTs) 126, 127, 156
- plasma-enhanced chemical vapor deposition (PECVD) method 87
- plasmonic perfect absorber (PPA) 72–76
- plasmon-enhanced photodetectors
- fabrication processes 39
 - InSe avalanche photodetector 43
 - nanostructures 36–38
 - preparation techniques 38
 - resonant properties 37
 - 2D materials 36, 44
- plasmonic perfect absorber (PPA) 72
- broadband 76
 - enhanced QDIP 74–76
 - 2DSHA 76
- plasmonic structured illumination microscopy (PSIM) 177
- point-spread function (PSF) 175
- polarization beam splitter (PBS) 128, 156, 253
- pristine 2D perovskites 35
- q**
- quantum dots (QD) 5, 35, 36, 64, 65, 74, 202, 205
- quantum-noise cancellation (QNC) 123, 136–143
- quantum noise locking (QNL) 126
- quick charge extraction 14
- r**
- reversible saturable optical fluorescence transitions (RESOLFT) microscopy 176
- s**
- Schottky barrier height (SBH) 19
- self-injection locking 246–248, 253
- semiconductor lasers 215–261
- semimetallic 2D materials 22
- single-molecule localization microscopy (SMLM) 176

- single-wall carbon nanotubes (SWCNTs) 35
- spatial frequency shift (SFS)
label-free recovery process 180
photonic waveguide 184–189
principle of 177–178
super-resolution imaging 178–184
- SPP-assisted illumination nanoscopy 199–203
- standard quantum limit (SQL) 123
- stochastic optical reconstruction microscopy (STORM) 176
- structured illumination microscopy (SIM) 176, 177
- super-resolution imaging
labeled 195–197
label-free 194–195
principle of 189–193
SPPs and metamaterials 197–206
- super-resolution microscopy 175–177, 198
- surface plasmon polaritons (SPPs) 40, 55, 83, 177
- surface plasmonic resonance (SPR)
55
complex permittivity 56–57
grating-coupled 60–61
plasma oscillations 56
prism-coupled 59–60
- two-dimensional metallic hole array 61–64
- waves 57–59
- t**
- traditional Sagnac interferometer (TSI) 143
- traditional thin-film materials 13
- transition-metal dichalcogenides (TMDs) 40
photoresponse 16, 17
responsivity 15
- transition-metal oxides (TMOs) 14
- transmagnetic (TM) plane wave 57
- tunable single-tone microwave signal generation
- free-running state 240–242
- mode-beating self-pulsations 242–244
- period-one (P1) oscillation 244–245
- sideband injection locking 245–248
- 2D materials-based photodetectors 14, 19, 25, 44, 49
- two-dimensional metallic hole array (2DSHA) 61–64
- 2D semiconductors 17, 21, 23, 46, 49
- v**
- van der Waals heterostructure 3–5, 14, 28, 34
- visible-light photodetectors 15–21

